



TATA INSTITUTE OF FUNDAMENTAL RESEARCH

Engineering electron-phonon interactions in noble metals with nanoscale interfaces

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Acknowledgemen



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Modulating electron-phonon interaction in metals

Aligning states in a quantum well with fermi level



Phys. Rev. Lett. **114**, 047002

Interfacial el-ph interaction



Nat Commun 8, 214 (2017)

Achieving low-frequency phonons with surfaces



50 nm Sn nanowires *Phys. Rev. B* 99, 064512

Optically driving the lattice



Phys. Rev. B 95, 024304

Electron scattering from surfaces



Polycrystalline Au nanoparticles

ACS Photonics 2021, 8, 3, 752–757

Stress



Proc. Natl. Acad. Sci. 2014, 111, 8712– 8716

Our approach

Dense network of nanoscale crystalline interfaces

Metal nanoparticles embedded inside a metallic matrix



Challenge

Not achieved: Bottom-up assembly of 'Metal' with nanoparticles

Electron tunneling effects: Coulomb blockade, Variable Range hopping, Activated transport

Nanoparticle

Surface Capping Agents-Ligands

Tunelling gap

Assembly of nanoparticles





Our approach: A bi-metallic nano-hybrid



Near identical lattice constants of Au and Ag : 4.078 Å and 4.085 Å

Chemical route – The process flow Ag(NP) – Au hybrid



Temperature-dependance of electrical resistivity



Resistivity – interface correlation

 ρ_0 : Resistivity at base temperature ~6 K



The Mott-Ioffe-Regel (MIR) Limit and 'bad metals'



MIR Limit:
$$k_F l = 1$$
 $\rho_{MIR}^{Au} = 24.6 \ \mu\Omega$ -m

$$\rho_{MIR} = \frac{3\pi^2\hbar}{e^2k_F(k_Fl)} = \frac{3\pi^2\hbar}{e^2k_F}$$

Mean-free path approaching inter-atomic distance





Gunnarsson, Calandra, Han Rev Mod Phys 2003 75, 1085

Resistivity saturation The Mott-Ioffe-Regel (MIR) Limit and 'bad metals'



Resistivity saturation

The Mott-Ioffe-Regel (MIR) Limit and 'bad metals'



Point-contact spectroscopy – A primer



Point-contact spectroscopy – A primer



Point-contact spectroscopy – A primer



Point contact spectroscopy of nanohybrid films



Electron-phonon coupling in metallic nanohybrid films



▶ **Universality:** $\rho_{300} \propto \lambda$, Electron-phonon coupling dominates high *T* resistivity in a wide class of materials

- \Box Significant increase in with F
- <u>arXiv:2405.14684v1</u>

Role of nanoscale interfaces



Charge doping from difference in onsite potential





Shift in Au 4f peak in XPS Charge doping Variation of EPC with interfacial charge transfer

Possible role of Coulomb interactions



Role of nanoscale interfaces: Theoretical insight



Charge doping from difference in onsite potential



 δn



Contributions to the electron-phonon matrix elements from Coulomb interactions of electrons to interfacial charge

 $g_{ce} \propto V_0(\delta n)$

 V_0 : Inter-site Coulomb repulsion



Charge distribution in a square lattice: 4×4 Ag sites surrounded by 8×8 Au sites

- arXiv:2405.14684v1
- Details coming out in another paper soon



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Summary

- Bottom-up metal-nanocomposite
- Unconventional metallic transport: Bad metals
- Buried interfaces of Ag and Au significantly enhance the electron-phonon coupling in noble metals, which have intrinsically the weakest coupling

Questions?

- Origin of high values of EPC
- Existence of metallic state in strong EPC regime
- No crossover to Anderson insulator even for strong disorder
- Possible coexistence of localized and itinerant electrons?

Stay tuned for **Arindam's talk on 26th July** for more details and results!

Thank you for your attention

EXTRA SLIDES

Scaling of electron-phonon scattering rate

Ignore any non-phonon temperature-dependent scattering



SK, TK Maji, .. A. Ghosh (<u>arXiv:2405.14684v1</u>)

Role of nanoscale interfaces





Structure



Motivation

Not achieved: Bottom-up assembly of 'Metal' with nanoparticles <u>Electron tunneling effects</u>: Coulomb blockade, Variable Range hopping, Activated transport

Nanoparticle

Assembly of nanoparticles



Motivation

Not achieved: Bottom-up assembly of 'Metal' with nanoparticles <u>Electron tunneling effects</u>: Coulomb blockade, Variable Range hopping, Activated transport







Tie et al. PRB 89, 155117 (2014)

A bi-metallic nano-hybrid



Structure





Resistivity – interface correlation





$$R = \frac{h}{e^2} \frac{(1-T_N)}{MT_N}$$
, $T_N = \frac{\lambda}{L+\lambda}$, M : no. of modes $= \frac{L^2}{\lambda_H^2}$





Mott-loffe-Regel limit!

Resistivity saturation

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Mean-free path approaching inter-atomic distance





Gunnarsson, Calandra, Han Rev Mod Phys 2003 75, 1085

Metal Nanoparticles-A primer:



The Mott-Ioffe-Regel (MIR) Limit and 'bad metals'



Chemical route – The process flow Ag(NP) – Au hybrid



Film for transport measurements

Ligand removal and cross-linking

Clustering

Resistivity saturation

The Mott-Ioffe-Regel (MIR) Limit and 'bad metals'







Bound in the residual resistivity (disorder) in the range $F \sim 0.4 - 0.8$ towards the MIR limit